

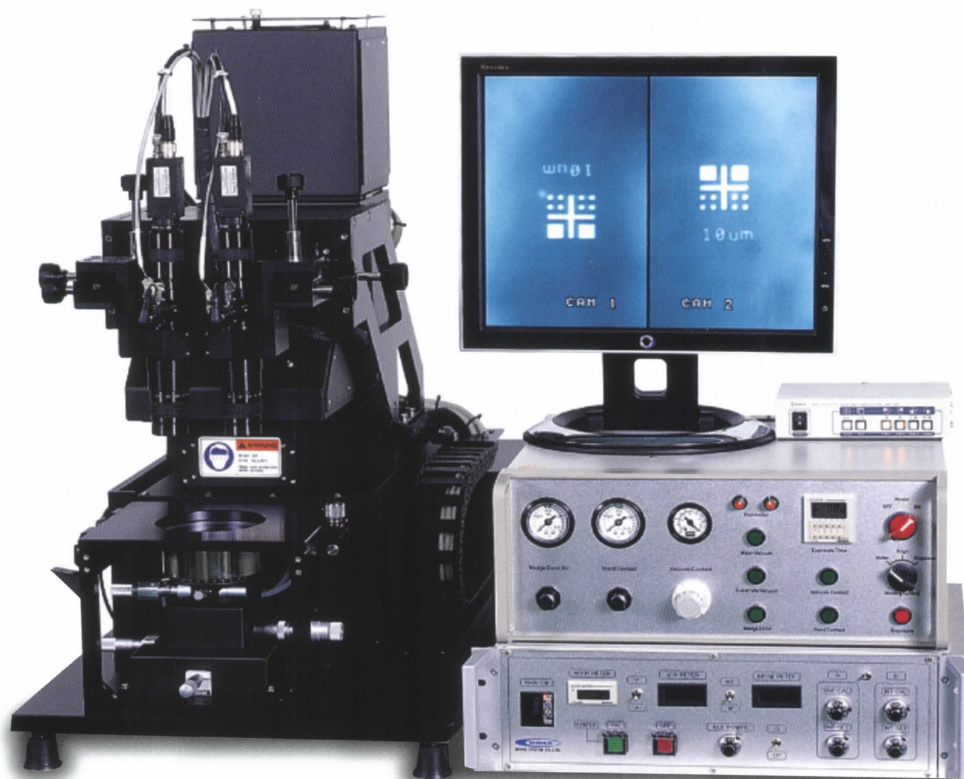
The Development and the commercialization of the Mask Aligner for wafer
Midas System will continue to grow along with the value creation for our customers.

MDA-400M

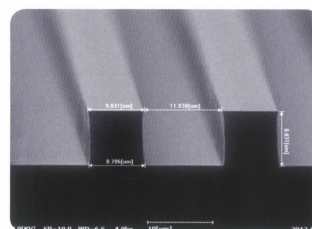
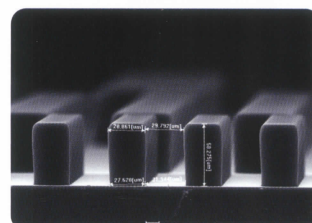
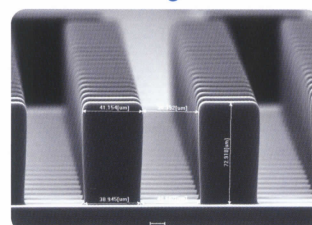
<http://www.aligner.co.kr>



The MDA-400M is widely used for MEMS, LED and semiconductor industry. This machine can make a higher performance of Alignment accuracy and resolution. It is ideal, economical unit for University and Research center.



▼ SEM Image



ITEM	SPECIFICATIONS
Substrate Size	Up to 4 inch
UV Lamp Power	350W
Resolution	1 μ m with 1 μ m thin PR @ Si wafer
Alignment Accuracy	1 μ m
Lamp Uniformity	$\leq \pm 3\%$
Uniform Beam Size	4.25" $\times$ 4.25"
365nm Beam Intensity	15~20mW/cm ²
Exposure Time	0.1 ~ 999.9 sec
Process mode	Vacuum, Hard, Soft and Proximity
Dimension	450 $\times$ 917 $\times$ 781 mm